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**Hatakeyama et al.**(10) **Pub. No.: US 2020/0192222 A1**(43) **Pub. Date: Jun. 18, 2020**(54) **RESIST COMPOSITION AND PATTERNING  
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**ABSTRACT**

A resist composition comprising an iodized base polymer and an iodized benzene ring-containing quencher has a high sensitivity and improved LWR and CDU.